Substitute Form (Modified)		Patent	partment of Commerce t and Trademark Office	Attorney's Docket No. Intel 10559-8870 P17697	Intel 10559-887001 / 10/		opplication No. 0/649,354	
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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate	
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1	1	AL/	Shu et al.; "Hard Pellicle Study for 157-nm Lithography," Preprint, to appear in the Proceedings of Photomask Japan, 2002			
		AM	Radiation Physics and Chemistry 62 (2001) 39-45; Oshioma et al.; "Chemical structure and physical properties of radiation-induced crosslinking of polytetrafluoroethylene"; www.elsevier.com/locate/radphyschem; © 2001 Elsevier Science Ltd.			
		AN	Reu et al.; "Mechanical analysis of hard pellicles for 157 nm lithography"; to appear in the Proceedings of the 2001 SPIE Symposium on Optical Microlithography XIV, Vol. 4346, 2001;			
		AO	Kozeki et al.; "Longevity of 193nm/ArF Excimer Pellicle"; April 26, 2001; Mitsui Chemicals, Inc., Pellicles Dept.			
1		АP	D.W. Van Krevelen, with collaboration of P.J. Hoftyzer; "Properties of Polymers, Their Estimation and Correlation with Chemical Structure," Second, completely revised edition, pp. 68-73; Elsevier Scientific Publishing Company, Amsterdam-Oxford-New York 1976			

Examiner Signature	Date Considered 6/20/05						
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